



GaN HEMT Characterization and Modeling using ASM-HEMT

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Nanolab – Characterization and Modeling Capabilities

An introduction to ASM-HEMT

Modeling Power Devices using ASM-HEMT

Modeling RF Devices using ASM-HEMT

Characterizing Self Heating and its Modeling

Trapping models in ASM-HEMT

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Nanolab: Characterization and Modeling Capabilities

- About Nanolab
- Hardware Capabilities
 - EDA Capabilities

About Nanolab: Some Stats

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Funding

- Government Agencies
- Industry Partners
- Compact Model Coalition (CMC)

	Publications					
	2020	2019	2018	2017	2016	2015
Books		1				1
Journal	16	14	20	19	18	9
Conference	9	15	19	11	30	30





Current Members

- Postdoc 5
- Ph.D. 27
- Ten PhDs graduated

About Nanolab: Collaborations



































SYNOPSYS° cādence™

About Nanolab: Areas of Research



Atomistic Simulation

Strong compute and storage infrastructure for atomistic simulations - paving the way for first principle studies of materials. Research topics include materials like VO2, V2O5, black phosphoros, TMDs like MoS2, phosphorene, borophene among many others.



DC and RF Device Characterization

State-of-the-art equipment for DC and RF characterization of packaged and on-wafer devices. High power measurement capabilities coupled with pulsed IV/RF and load pull systems allow for characterizations of higher level circuits like power amplifiers.



RF Circuit Design

Strong collaboration with the industry in terms of model development. Working closely with UC Berkeley to maintain and develop the BSIM standard models. Out ASM-HEMT model for GaN-HEMTs was recently recognized as an

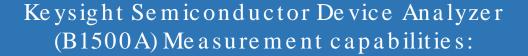
industry standard by the Compact Model Coalition (CMC)

SPICE/Compact Modeling

Hardware and software capabilities to design and implement prototypes for RF circuits. Power Amplifier and Low Noise Amplifier design using advanced device technologies.

Hardware Capabilities I





- IV, CV, pulse/dynamic IV range of 0.1 fA 1 A / 0.5 μV 200 V
- Evaluation of devices, materials, semiconductors, active/passive components
- AC capacitance measurement in multi frequency from 1 kHz to
 5 MHz
- Pulsed IV measurement min 10 ns gate pulse width with 2 ns rise and fall times with 1 µs current measurement resolution



Maury Microwaves/ AMCAD AM3221

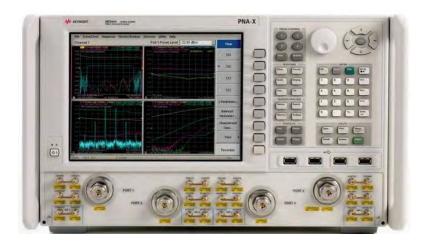
- Bipolar ±25V/ 1A (gate) and high-voltage 250 V/ 30 A (drain) models
- Pulse widths down to 200ns
- Synchronized pulsed S-parameter measurements
- Connect systems in series for synchronizing 3+pulsed channels
- Long pulses into the tens and hundreds of seconds for trapping and thermal characterization

Hardware Capabilities II



Keysight ENA (E5071C) 100KHz to 8.5 GHz

- 9 kHz to 4.5/6.5/8.5/14/20 GHz
- 2- or 4-port, 50-ohm, S-parameter test set
- Improve accuracy, yield and margins with wide dynamic range 130 dB, fast measurement speed 8ms and excellent temperature stability 0.005 dB/°C



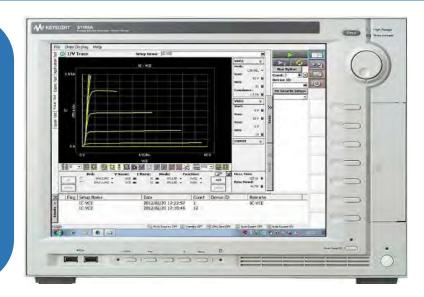
Keysight PNA-X (N5244A) 10 MHz to 43.5 GHz

- High Frequency Device Characterization (Microwave Network Analyzer)
- 100 Khz to 8.5 GHz and 10 MHz to 43.5 GHz
- 2-port and 4-ports with two built-in sources
- High output power (+16 dBm)
- Best dynamic accuracy: 0.1 dB compression with +15 dBm input power at the receiver
- Low noise floor of -111 dBm at 10 Hz IF bandwidth

Hardware Capabilities III

Keysight Power Device Characterization System: B1505

- Power device characterization up to 1500 A & 10 kV
- Medium current measurement with high voltage bias (e.g. 500 m A at 1200 V)
- $-\mu\Omega$ on-resistance measurement capability
- Accurate, sub-picoamp level, current measurement at high voltage bias
- Fully automated Capacitance measurement at up to 3000 V of DC bias
- High power pulsed measurements down to 10 μs
- High voltage/high current fast switch option to characterize GaN current collapse effect
- Fully automated thermal testing from -50 °C to +250 °C





Keysight N8975B Noise Figure Analyzer

- Frequency range 10 MHz to 26.5 GHz in a one-box solution
- Includes Spectrum Analyzer and IQ Analyzer (Basic) modes
- SNS series noise source N4002A
- U7227C 100 MHz to 26.5 GHz External USB Preamplifier included

Load Pull Characterization

Maury Load Pull Characterization system

- A fundamental passive load pull system capable of performing load pull characterization up to 15W.
- XT982GL01 0.6 to 18 GHz
 Load tuner
- Plan to expand to a 3
 harmonic hybrid load pull system soon.



EDA Capabilities

SPICE SIMULATORS



cādence



cādence

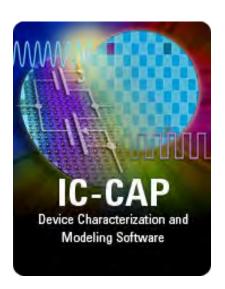




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TCAD





Atomistic Simulations

Quantum Wise Nextnano

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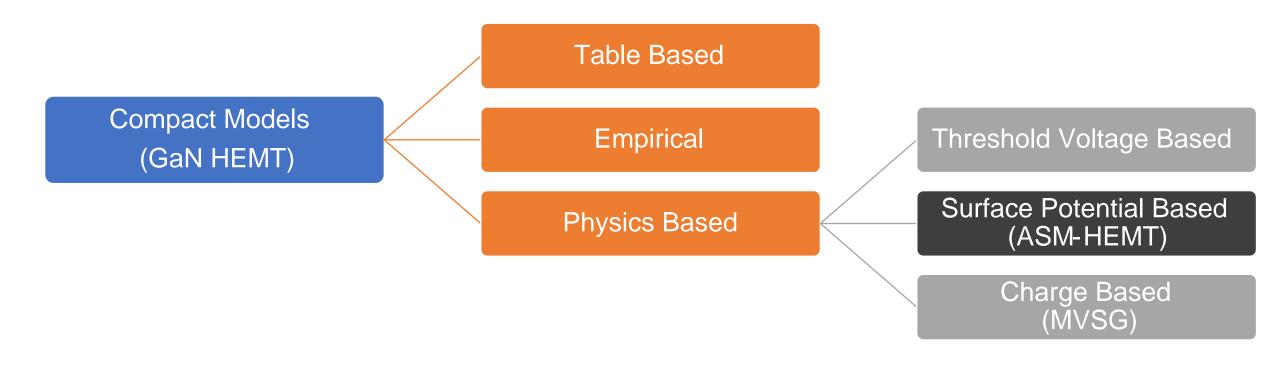
An introduction to ASM - HEMT

- About ASM-HEMT and its core
 - Extraction flow
- Other models incorporated into the core
 - Geometric Scaling

A brief history of HEMT models

FET Models	Approx. Number of Parameters	Electrothermal (Rth-Cth) Model	Geometry Scalability Built-In	Original Device Context
Curtice3 [12]	59	No	No	GaAs MESFET
Motorola Electrothermal (MET) [25]	62	Yes	Yes	LD MOSFET
CMC (Curtice/ Modelithics/Cree) [26]	55	Yes	Yes	LD MOSFET
BSIMSOI3 [24]	191	Yes	Yes	SOI MOSFET
CFET [5]	48	Yes	Yes	HEMT
EEHEMT [13]	71	No	Yes	HEMT
Angelov [14]	80	Yes	No	HEMT/MESFET
Angelov GaN [11]	90	Yes	No	HEMT
Auriga [4]	100	Yes	Yes	HEMT

Various classes of compact models



Advanced SPICE Model for GaN HEMTs (ASM-HEMT)



www.iitk.ac.in/asm



Prof. Yogesh Singh Chauhan



Dr. Sudip Ghosh



Dr. Aamir Ahsan



Dr. Avirup Dasgupta



Ahtisham Pampori



Raghvendra Dangi

ASM-HEMT: Summary

Electrostatics

Analytical Solution of Schrodiger's & Poisson's



2-DEG Charge, Ef, Surface Potential

Transport

SP-Based Current & Charge Model



I-V, C-V, DIBL, Rd, Rs, Vel. Sat., ...

Higher-order Effects

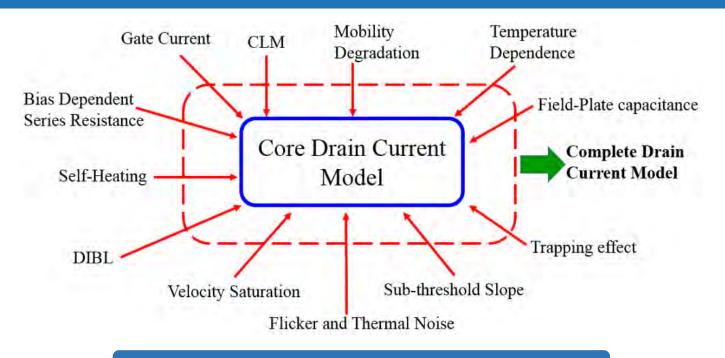
Noise, Trapping, Self-Heating, Field Plate



DC, AC, Transient Harmonic Sim., Noise, ...

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ASM-HEMT: Core Model



Core Model Parameters

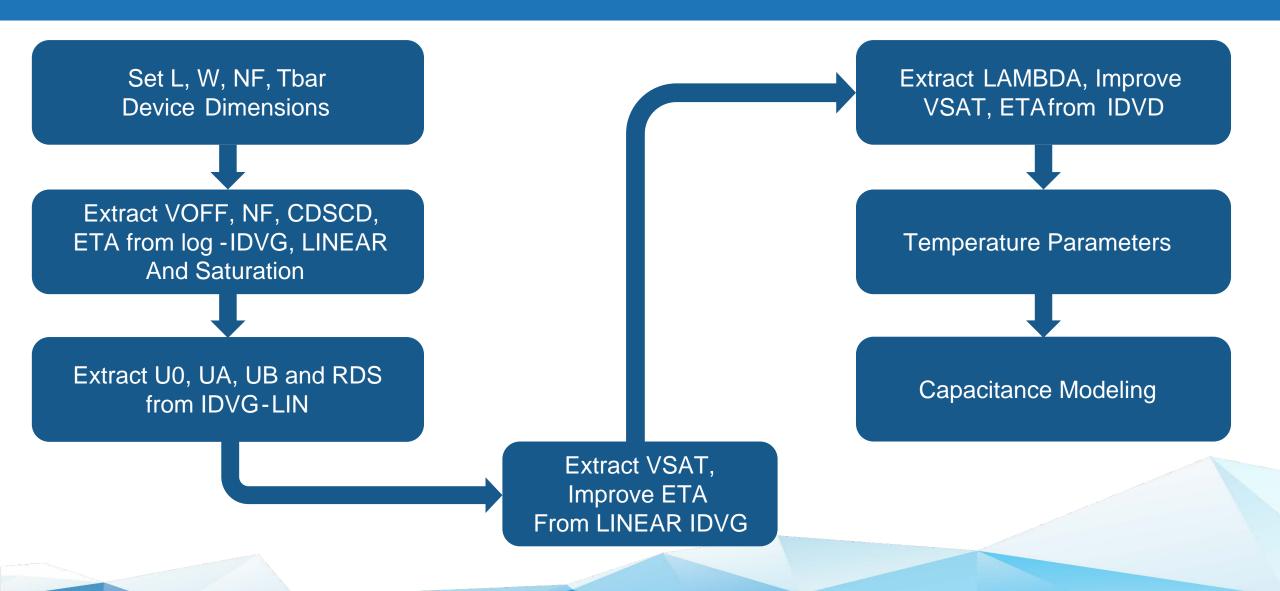
Parameter	Description	Extracted Value		
V_{OFF}	Cutoff Voltage	-2.86 V		
N_{FACTOR}	Subthreshold Slope Factor	0.202		
C_{DSCD}	SS Degradation Factor	$0.325 V^{-1}$		
η_0	DIBL Parameter	0.117		
U_0	Low Field Mobility	$33.29 mm^2/Vs$		
N_{S0ACCS}	AR 2DEG Density	$1.9e + 17 / m^2$		
$V_{SATACCS}$	AR saturation velocity	157.6e + 3 cm/s		
R_{TH0}	Thermal Resistance	22 Ω		

Real Device Effects Incorporated into the Model

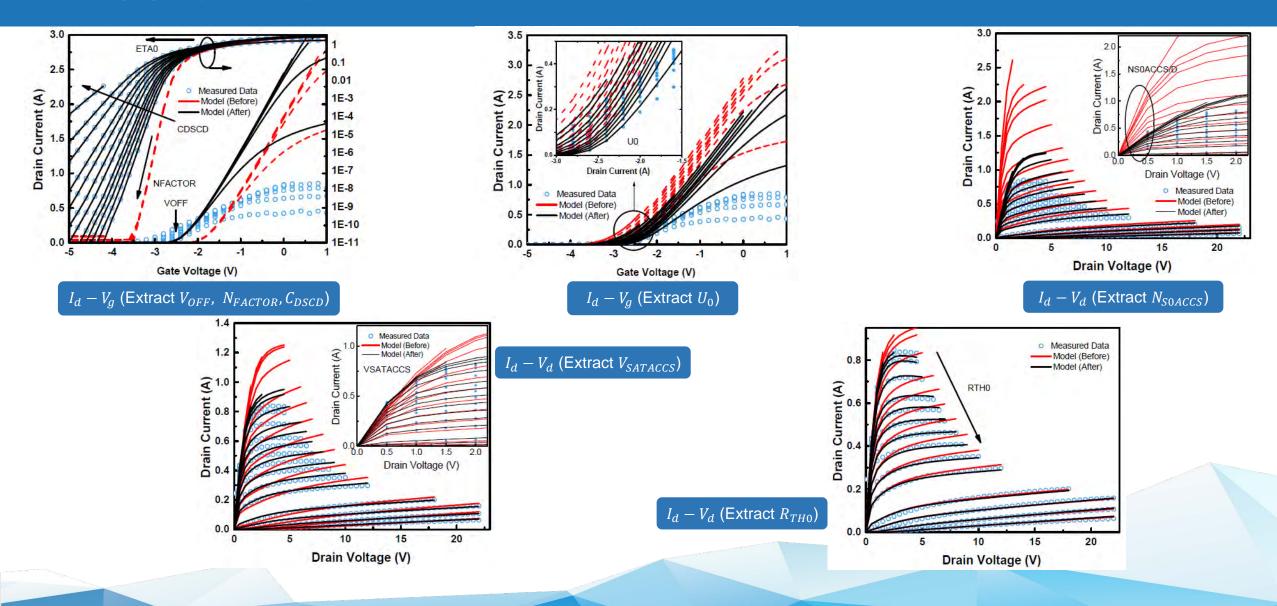
Core drain current expression

$$I_{ds} = \frac{\mu_{eff}}{\sqrt{1 + \theta_{sat}^2 \psi_{ds}^2}} \frac{W}{L} C_g N_f \left[V_{go} - \left(\frac{\psi_s + \psi_d}{2} \right) + V_{th} \right] \times \psi_{ds}$$

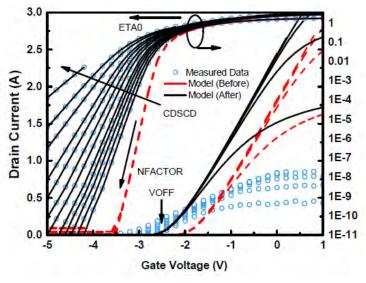
Extraction Flow I

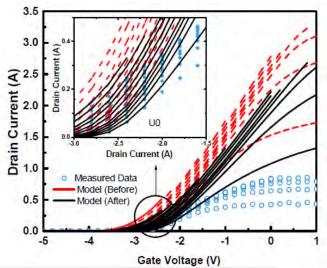


Extraction Flow II



Extraction from Id - Vg curves





Start with $I_d - V_g$ characteristics in the log scale

ETA0 – DIBL Parameter

NFACTOR – Sub-threshold slope parameter

CDSCD – Captures the drain voltage dependence on the subthreshold slope.

VOFF – Cut-Off Voltage

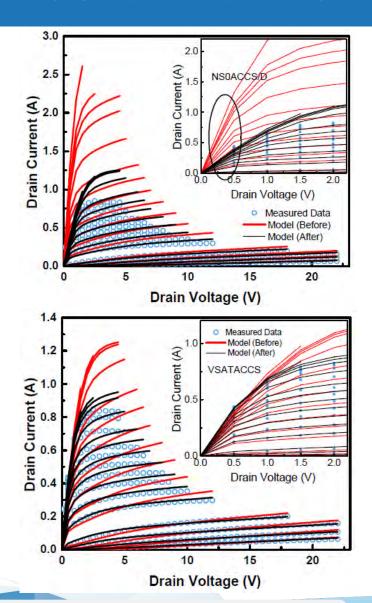
 $I_d - V_g$ characteristics in the linear scale

U0 – Low field mobility

UA, UB – Mobility degradation parameters

[1] S. A. Ahsan et al., IEEE J. Electron Devices Society, Sep., [2017]

Extraction from Id - Vd curves



 $I_d - V_d$ characteristics

VSAT – Velocity saturation parameter

UA, *UB* – Mobility degradation parameters

Access Region Parameters extracted from $I_d - V_d$ characteristics:

NSOACCS(D) – 2DEG density in the access region.

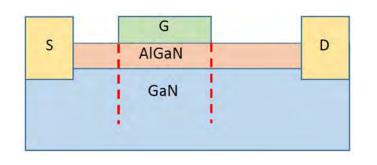
VSATACCS – Saturation velocity in the access region.

U0ACCS(D) – Low field mobility in the access region.

VOACCS(D) independently tunes the access region resistance around $Volume{ds} = 0$ and helps extract g_{ds} at that point.

[1]S. A.Ahsan et al., IEEE J. Electron Devices Society, Sep., [2017]

Bias-dependent access region resistance model: Overview

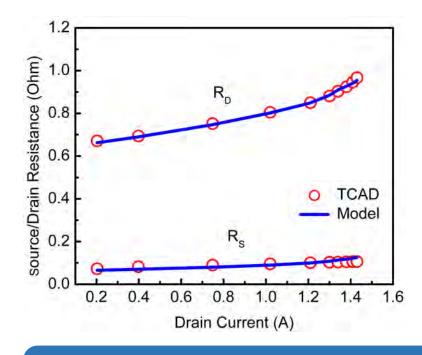


$$R_J = \frac{L_J}{q\mu_n n_{s0}} \qquad J = S, D$$
 Intrinsic D Rs = f(Vg, Vd) Rd = f(Vg, Vd)

$$I_{acc} = Q_{acc} \cdot v_s = Q_{acc} \cdot v_{sat} \cdot \frac{V_R/V_{Rsat}}{\left[1 + \left(\frac{V_R}{V_{Rsat}}\right)^{\gamma}\right]^{\frac{1}{\gamma}}}$$

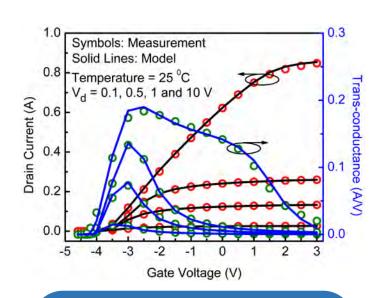
$$R_{d/s} = \frac{V_R}{I_{acc}} = \frac{R_{d0/s0}}{\left[1 - \left(\frac{I_d}{I_{acc,sat}}\right)^{\gamma}\right]^{\frac{1}{\gamma}}}$$

$$I_{\rm ds,acc} = \frac{R_{\rm c}}{W \cdot N_{\rm f}} + \frac{L_{\rm acc}}{W \cdot N_{\rm f} \cdot q \cdot N_{\rm S0ACCS} \cdot U_{\rm 0ACCS}} \times \left(1 - \left(\frac{I_{\rm ds}}{W \cdot N_{\rm f} \cdot N_{\rm S0ACCS} \cdot V_{\rm SATACCS}}\right)^2\right)^{-1/2}$$



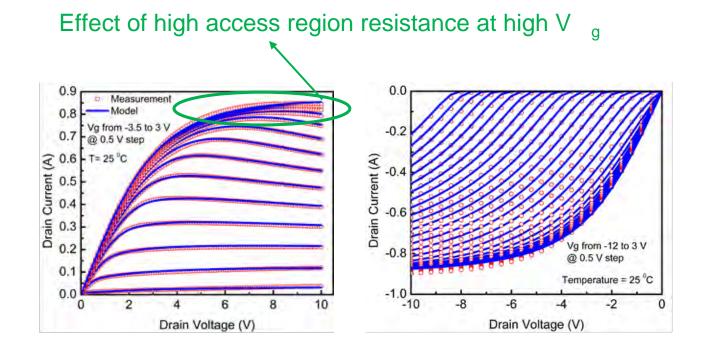
Nonlinear variation of source/ drain access resistances with Ids extracted from TCAD simulation and comparison with model.

Bias-dependent access region resistance model: Results



Id - Vg and trans - conductance for the Toshiba power HEMT.

Different slopes above Voff in gm - Vg: self-heating governs the first slope while velocity saturation in access region affects second slope.



Ids-Vds and reverse Ids-Vds fitting with experimental data. The non -linear Rs/d model shows correct behavior for the higher Vg curves in the Id - Vd plot; the S-P based model can accurately capture the reverse output characteristics.

Bias-dependent access region resistance model: Temperature scaling

The temperature dependence of R _{d/s} model is extremely important as it increases significantly with increasing temperature

Temperature dependence of 2 -DEG charge density in the drain or source side access region:

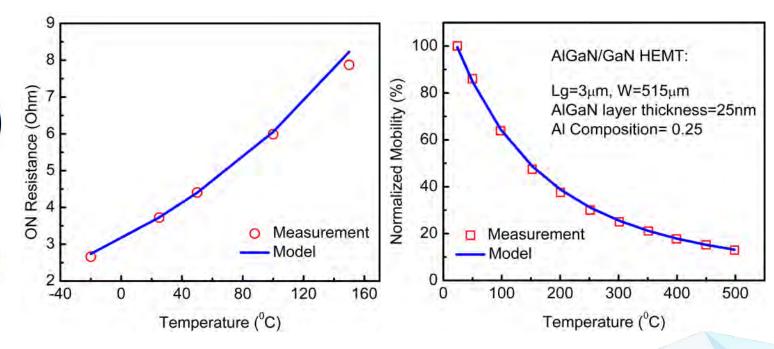
$$n_{s0}(T) = NS0ACC \cdot \left(1 - KNS0 \cdot \left(\frac{T}{TNOM} - 1\right)\right)$$

Temperature dependence of Saturation Velocity:

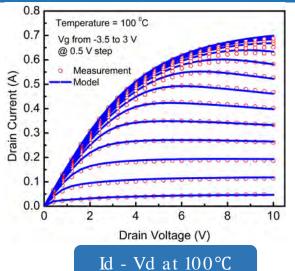
$$V_{sat}(T) = VSATACCS \cdot [1 + ATS(T - TNOM)]$$

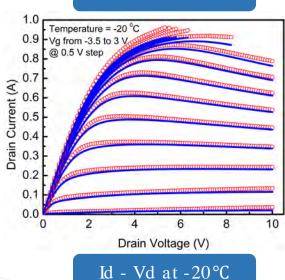
Temperature dependence of electron Mobility:

$$\mu_{acc}(T) = U0ACC \cdot \left(\frac{T}{TNOM}\right)^{UTEACC}$$



ASM-HEMT: Temperature scaling results



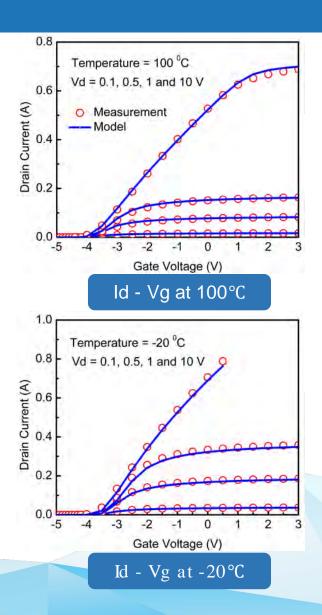


ASM-HEMT features a robust temperature scaling model which has been validated across a broad range of device temperatures.

$$\begin{split} &V_{off,DIBL}(T) \\ &= V_{off,DIBL} - \left(\frac{T_{dev}}{T_{NOM}} - 1\right) \cdot \textit{KT1} + TRAPVOFF \\ &\cdot vcap + voff_{trap} \end{split}$$

$$U0(T) = U0 \cdot \left(\frac{T_{dev}}{T_{NOM}}\right)^{UTE}$$

$$VSAT(T) = VSAT \cdot \left(\frac{T_{dev}}{T_{NOM}}\right)^{AT}$$



[1] S. Ghosh et al., IEEE International Conference on Electron Devices and Solid-State Circuits (EDSSC), [2016]

Geometric Scaling I

Charge Scaling

$$Q_{g} = \frac{C_{g}LW}{V_{g0} - \psi_{m} + V_{tv}} [V_{g0}^{2} + \frac{1}{3}(\psi_{d}^{2} + \psi_{s}^{2} + \psi_{d}\psi_{s}) - V_{g0}(\psi_{d} + \psi_{s} - V_{tv}) - V_{tv}\psi_{m}]$$

$$Q_{d} = -\frac{C_{g}LW}{120(V_{g0} - \psi_{m} + V_{tv})^{2}} [12\psi_{d}^{3} + 8\psi_{s}^{3} + \psi_{s}^{2}(16\psi_{d} - 5(V_{tv} + 8V_{g0})) + 2\psi_{s}(12\psi_{d}^{2} - 5\psi_{d}(5V_{tv} + 8V_{g0}) + 10(V_{tv} + V_{g0})(V_{tv} + 4V_{g0})) + 15\psi_{d}^{2}(3V_{tv} + 4V_{g0}) - 60V_{g0}(V_{tv} + V_{g0})^{2} + 20\psi_{d}(V_{tv} + V_{g0})(2V_{tv} + 5V_{g0})]$$

Current Scaling

$$I_d = \frac{W}{L} \mu C_g (V_g 0 - \psi_m + V_{th}) \psi_{ds}$$
Where $\psi_m = (\psi_d + \psi_s)/2$, $\psi_d s = (\psi_d - \psi_s)$

Access Region Resistance Scaling

$$\begin{split} R_{source} = & \frac{RSC(T)}{W \cdot NF} + TRAPRS \cdot vcap \\ & + \frac{LSG}{W \cdot NF \cdot q \cdot NS0ACCS(T) \cdot U0ACCS(T)} \\ & \cdot \left(1 - \left(\frac{I_{ds}}{I_{sat,source}}\right)^{MEXPACCS}\right)^{\frac{-1}{MEXPACCS}} \end{split}$$

where

$$I_{sat, source} = W \cdot NF \cdot NS0ACCS(T) \cdot VSATACCS(T)$$

$$\begin{split} R_{drain} = & \frac{RDC(T)}{W \cdot NF} + TRAPRD \cdot vcap + R_{trap}(T) + ron_{trap} \\ & + \frac{LDG}{W \cdot NF \cdot q \cdot NS0ACCD(T) \cdot U0ACCD(T)} \\ & \cdot \left(1 - \left(\frac{I_{ds}}{I_{sat,source}}\right)^{MEXPACCD}\right)^{\frac{-1}{MEXPACCD}} \end{split}$$

where
$$I_{sat,drain} = W \cdot NF \cdot NS0ACCD(T) \cdot VSATACCS(T)$$

Geometric Scaling II

Thermal Noise and Flicker Noise Scaling

$$S_{if}(f) = \frac{k_{B}T}{WL^{2}f^{EF}} \frac{I_{DS}^{2}K_{r}}{C_{g}^{2}} \left[NOIAV_{th}C_{g} \left(\frac{1}{Q_{ch,d}} - \frac{1}{Q_{ch,s}} \right) + (NOIA + NOIBV_{th}C_{g})ln \left(\frac{Q_{ch,d}}{Q_{ch,s}} \right) + (NOIB + NOICV_{th}C_{g})(-Q_{ch,d} + Q_{ch,s}) + \frac{NOIC}{2}(Q_{ch,d}^{2} - Q_{ch,s}^{2}) \right]$$

$$S_{it} = \frac{4k_{B}T_{dev}}{I_{D}L_{eff}^{2}} \left(\mu_{eff,sat}WqC_{g} \right)^{2} \left(V_{go}^{2}\psi_{ds} + \frac{\psi_{d}^{3} - \psi_{s}^{3}}{3} - V_{go} \left(\psi_{d}^{2} - \psi_{s}^{2} \right) \right)$$

$$+ (NOIB + NOICV_{th}C_{g})(-Q_{ch,d} + Q_{ch,s}) + \frac{NOIC}{2}(Q_{ch,d}^{2} - Q_{ch,s}^{2}) \right]$$

Gate Current Scaling

$$I_{gs} = W \cdot L \cdot NF \cdot \left[IGSDIO + \left(\frac{T_{dev}}{TNOM} - 1 \right) \cdot KTGS \right] \left[exp \left\{ \frac{V_{gs}}{NJGS \cdot K_B \cdot T_{dev}} \right\} - 1 \right]$$

$$I_{gd} = W \cdot L \cdot NF \cdot \left[IGDDIO + \left(\frac{T_{dev}}{TNOM} - 1 \right) \cdot KTGD \right] \left[exp \left\{ \frac{V_{gd}}{NJGD \cdot K_B \cdot T_{dev}} \right\} - 1 \right]$$

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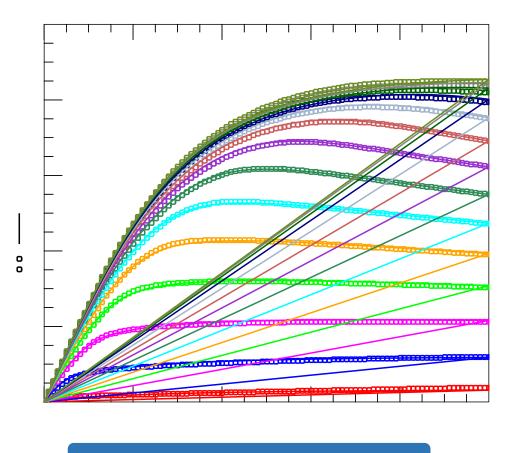




Modeling Power Devices using ASM - HEMT

- Modeling DC
- Modeling field plates
- Model comparison with a mixed mode device

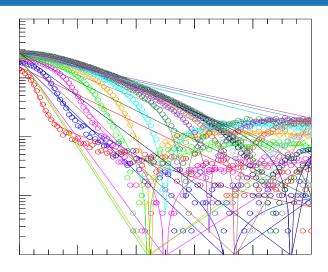
Modeling DC: Room Temperature Output Characteristics

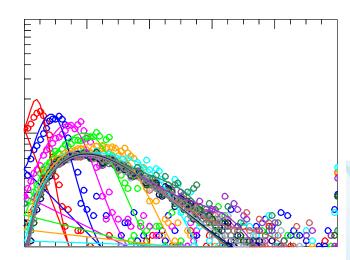


Output conductance versus Vd

ASM-HEMT accurately captures the IV characteristics of a power GaN HEMT device.

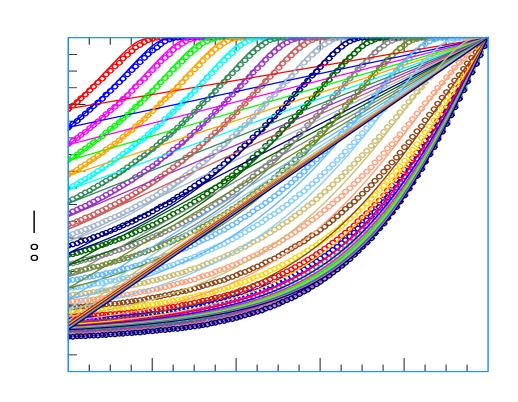
Derivative of output conductance versus Vd





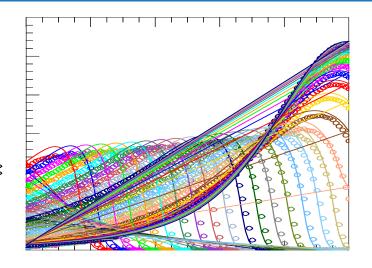
Output Characteristics at T=25 °C

Modeling DC: Room Temperature Reverse Output Characteristics

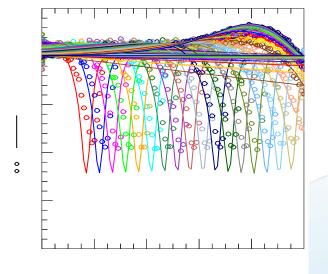


Reverse Output Characteristics at $T=25^{\circ}C$

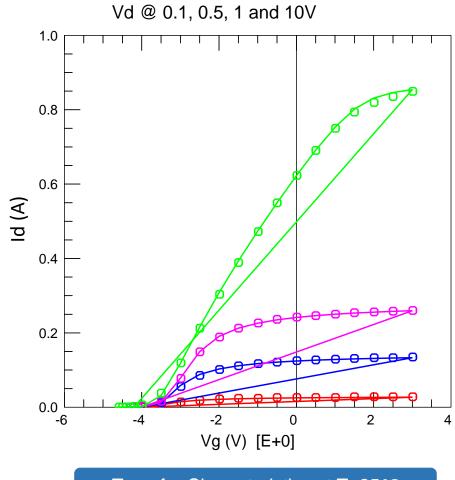
Reverse Output conductance versus Vd



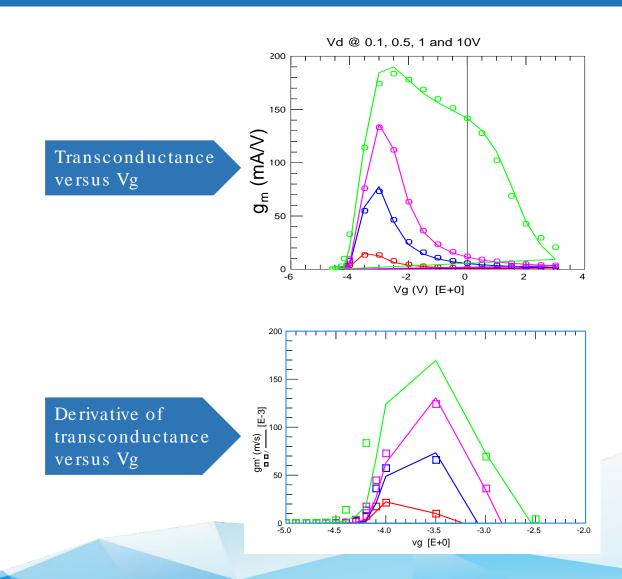
Derivative of reverse output conductance versus Vd



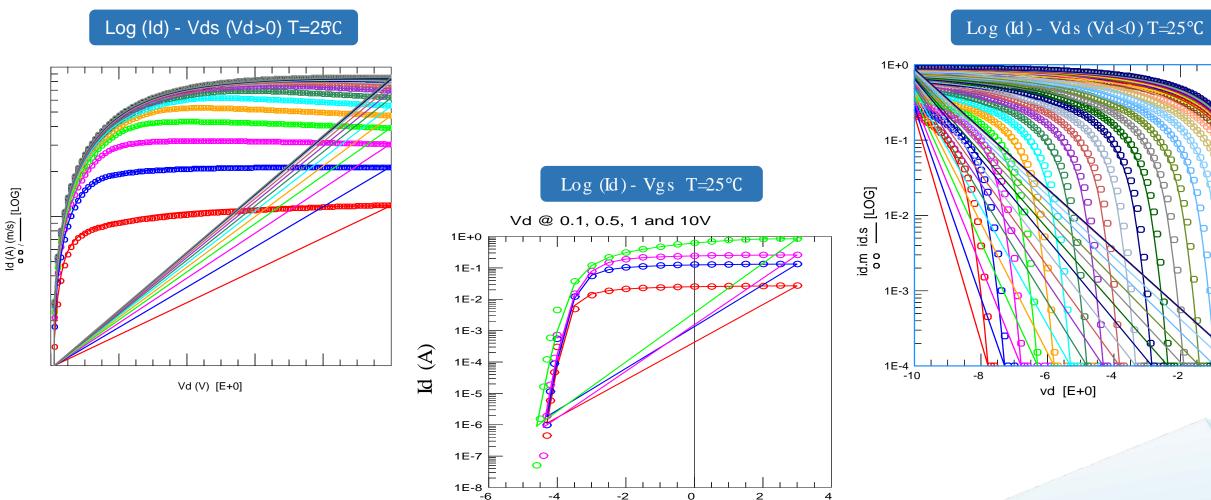
Modeling DC: Room Temperature Transfer Characteristics

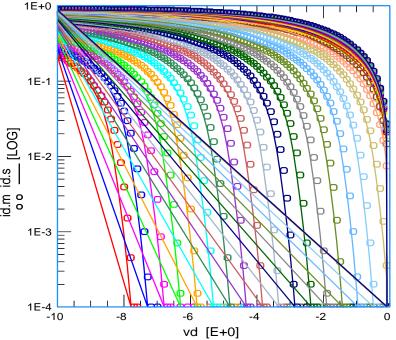






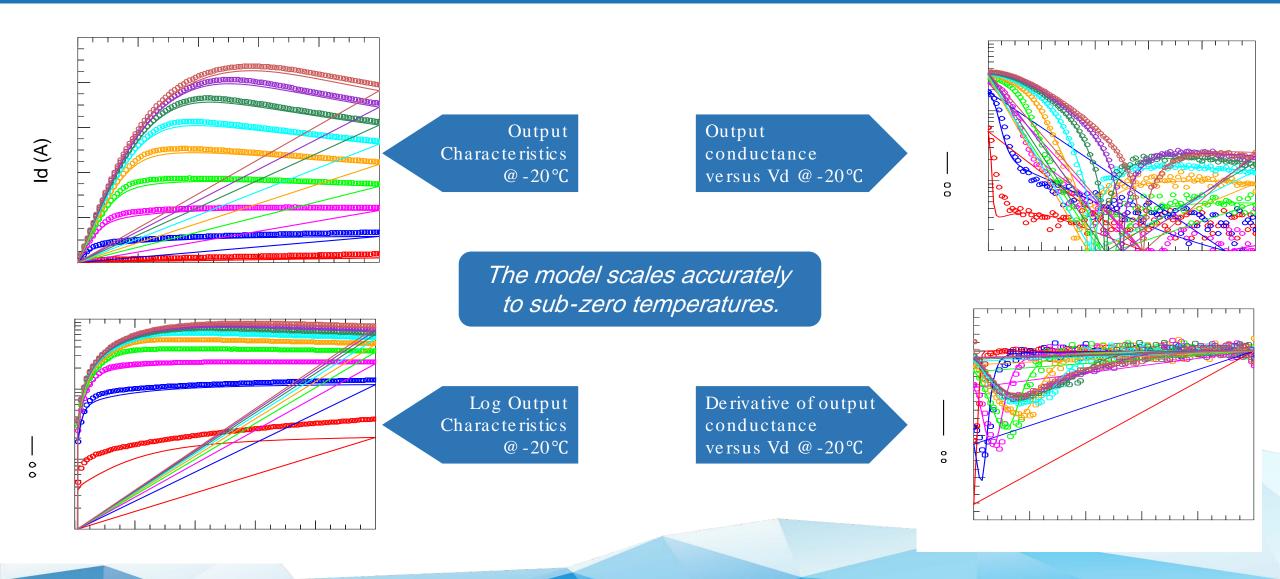
Modeling DC: Room Temperature IV – Log Scale



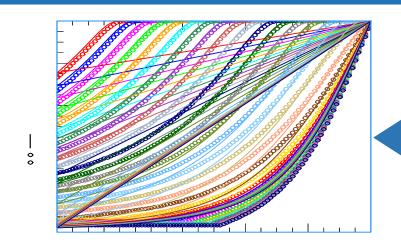


Vg (V) [E+0]

Modeling DC: Output Characteristics @ T=-20°C

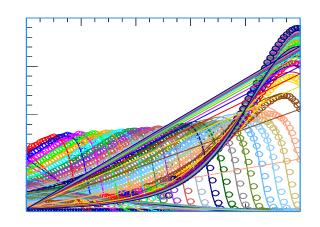


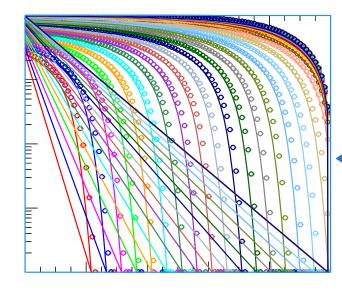
Modeling DC: Reverse Output Characteristics @ T=-20°C



Vg from -12 to 3 V @ 0.5V step

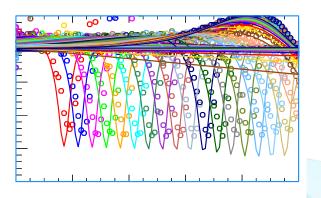
Reverse Output Characteristics @-20°C Reverse Output conductance versus Vd @-20°C





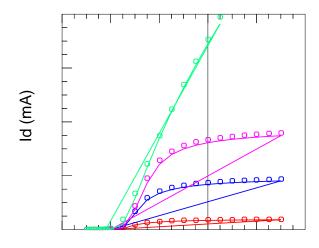
The model scales accurately to sub-zero temperatures.

Log Output Characteristics @-20°C Derivative of reverse output conductance versus Vd @-20°C

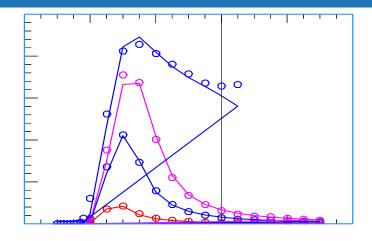


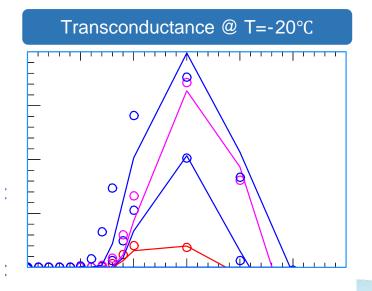
Modeling DC: Transfer Characteristics @ T=20°C

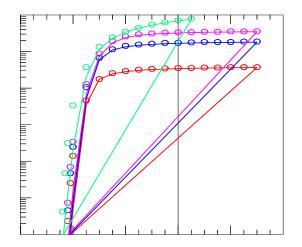
The model scales accurately to sub-zero temperatures.



Transfer Characteristics @ T=-20°C



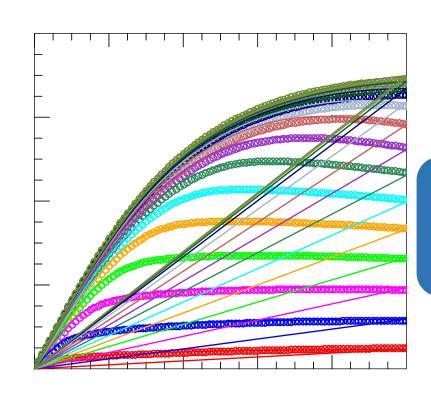




Transfer Characteristics (Log) @ T=-20°C

Derivative of Transconductance @ T= -20°C

Modeling DC: IV Characteristics @ T=100°C



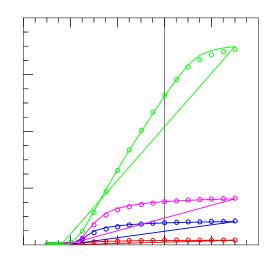
Id (mA)

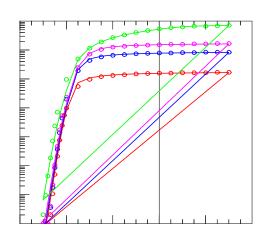
Transfer Characteristics @ T=10°C

ld (mA)

The model can accurately capture high temperature operation of the device.
This is particularly important for power devices which generate a lot of heat.

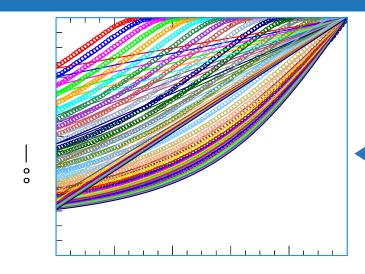
Transfer
Characteristics
(Log) @ T=100C





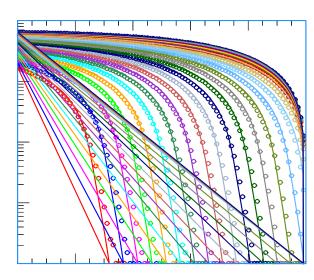
Output Characteristics @ T=100°C

Modeling DC: Reverse Output Characteristics @ T=150°C



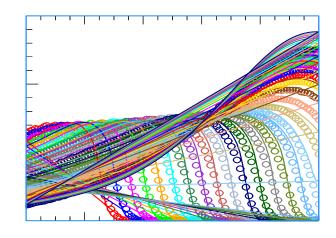
Vg from -12 to 3 V @ 0.5V step

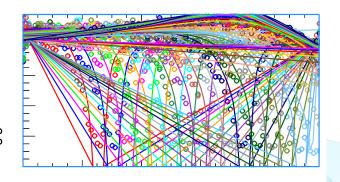
Reverse Output Characteristics @ 150°C Reverse Output conductance versus Vd @ 150°C



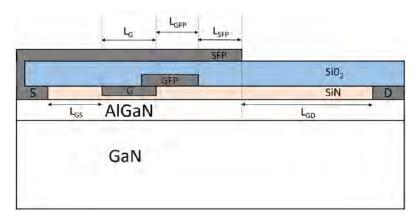
The model can accurately capture high temperature operation of the device.
This is particularly important for power devices which generate a lot of heat.

Log Output Characteristics @ 150°C Derivative of reverse output conductance versus Vd @ 150°C

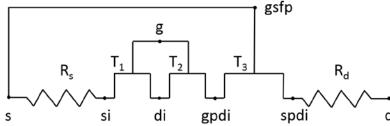




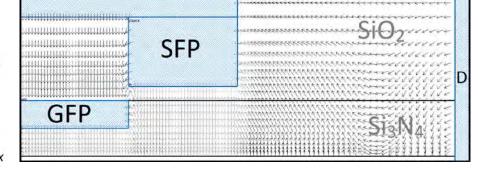
Modeling field plates: Structure



Field plates flatten out the peak in the electric field caused by the sudden drop in potential at the gate edge. TCAD showing field fluctuations leading to a distributed field inside the device.

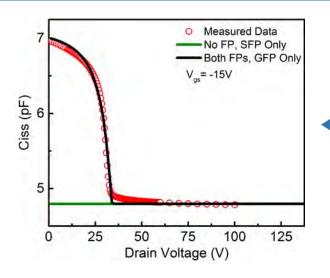


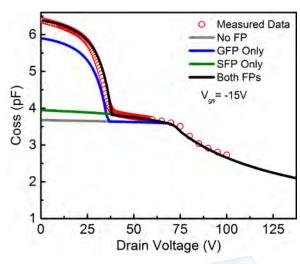
head foot $|E| \int_{x_{\rm S}}^{x_{\rm D}} E_x \, \mathrm{d}x = -V_{\rm DS}$



A Gate Field Plate (GFP) and a Source Field Plate (SFP) structure modeled as transistors in series.

Modeling field plates: Trends w.r.t Drain Voltage



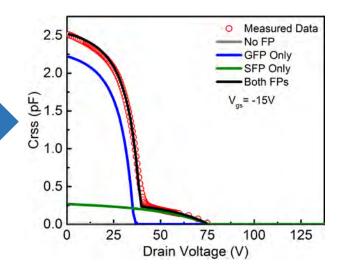


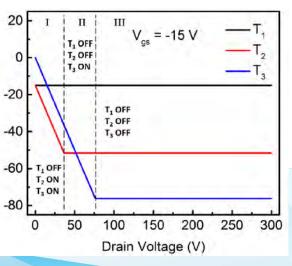
Terminal Capacitance: Input side (Ciss) Terminal Capacitance: Reverse (Crss)

The plateaus in each capacitance curve denote the **switching -off** of one of the transistors in series as depicted in the previous slide.

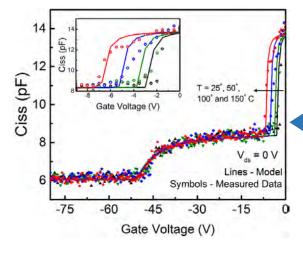
Terminal Capacitance:
Output side (Coss)

Activation of different series transistors with increasing drain voltage at a fixed gate bias



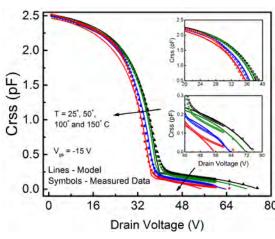


Field Plate Models: Trends w.r.t temperature



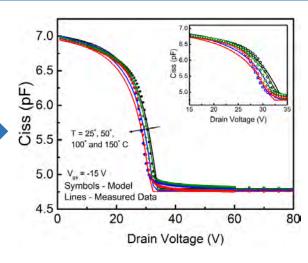
Terminal Capacitance: Input side (Ciss) with gate voltage

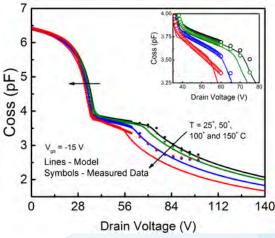
Terminal Capacitance: Input side (Ciss) with drain voltage



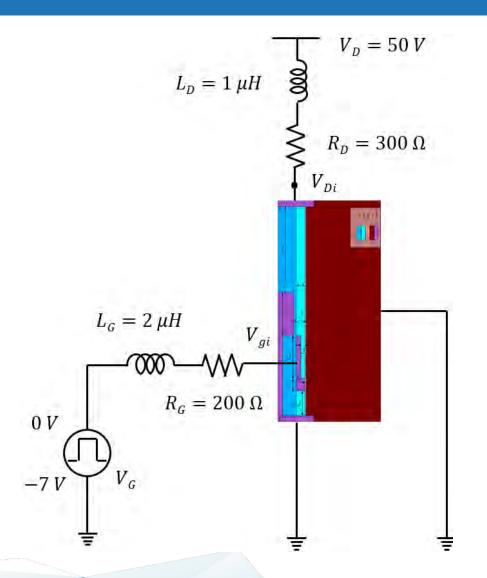
Increasing temperature shifts the threshold voltage in the negative direction — leading to a corresponding shift in the capacitance curves.

Terminal Capacitance: Reverse (Crss) Terminal Capacitance: Output side (Coss)



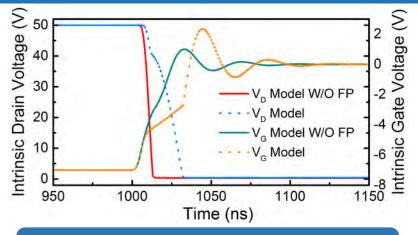


Mixed mode TCAD circuit using ATLAS

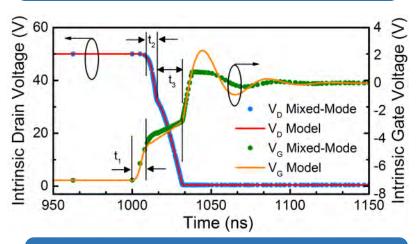


- Schematic for Mixed-mode simulation using the numerical GaN FP device generated in Atlas.
- The FP-HEMT is put as the DUT with 7 V and 0 V pulses of 1 MHz at gate.
- The pulse has a pulse-width of 480 ns 20 ns rise and fall times.
- Supply voltage of 50 V is chosen to capture the maximum effect of cross coupling capacitances on switching transients while an inductive load is put at the drain.

Voltage waveforms

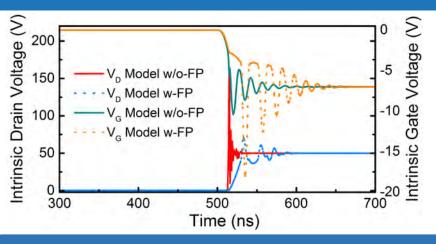


Turn-on by switching applied gate signal from 7 V to 0 V (FP vs no FP)

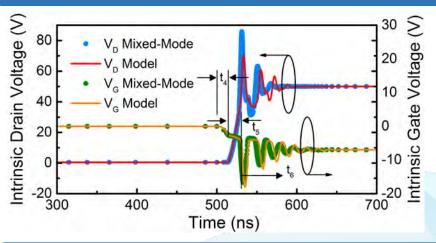


Turn-on by switching applied gate signal from V to 0 V (Mixed-mode vs Model)

The model accurately predicts drain overshoots due to LC ringing, Miller plateaus due to accurate prediction in sharing of the gate drive current to charge Cgs and Cgd and the associated gate -drain charge, and the damping of the oscillations.

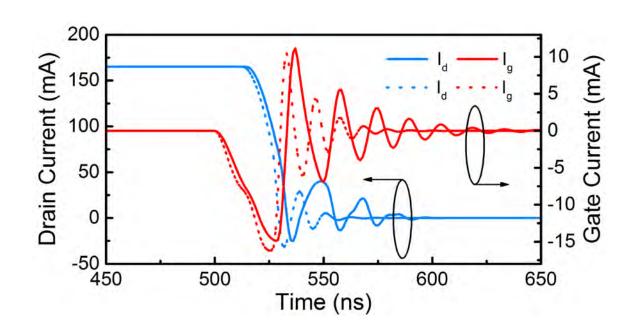


Turn-off by switching applied gate signal from 0 V to 7 V keeping applied drain voltage fixed at 50 V (FP vs No FP)



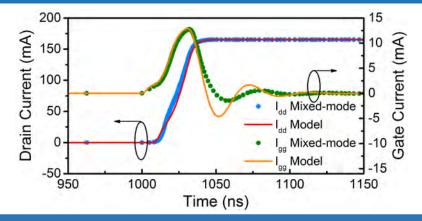
Turn-off by switching applied gate signal from 0 V to 7 V keeping applied drain voltage fixed at 50 V (Mixed -mode vs Model)

Current Waveforms

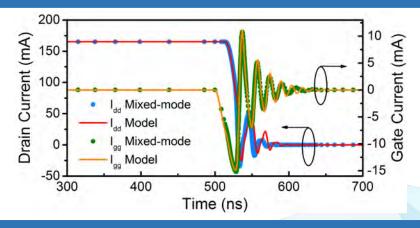


Comparison of modeled time -domain waveforms during turn -off with and without cross -coupling and substrate capacitances.

Solid lines = Cross-Coupling(CC) and substrate model included Dotted lines = CC and substrate model excluded.



Turn-on by switching applied gate signal from 7 V to 0 V (Mixed-mode vs Model)



Turn-off by switching applied gate signal from 0 V to 7 V, keeping applied drain voltage fixed at 50 V (Mixed-mode vs Model)

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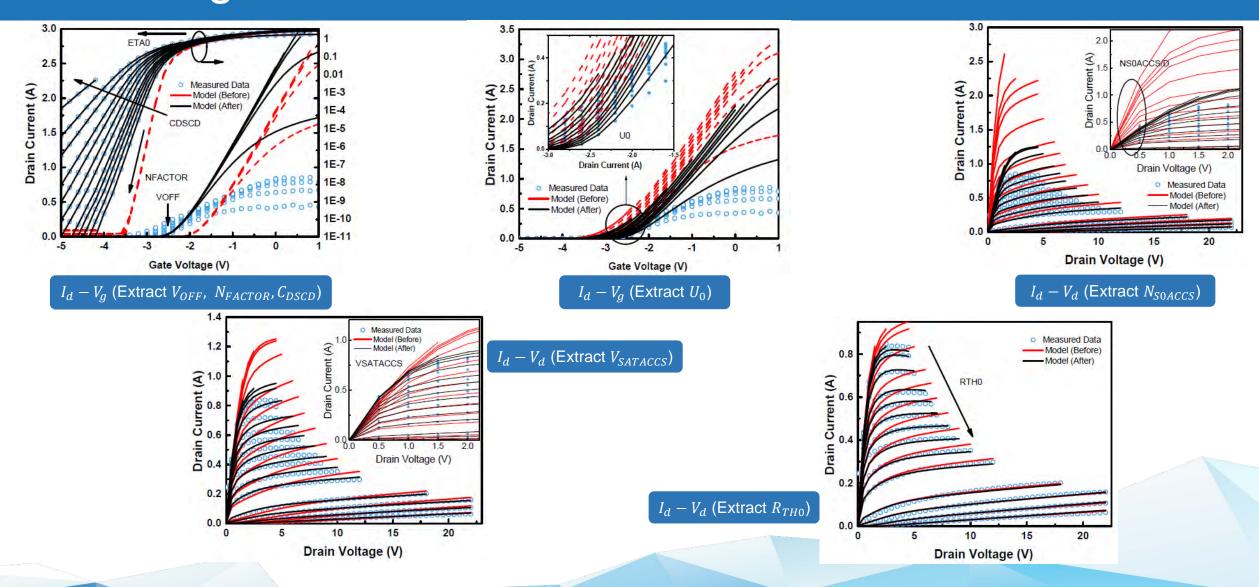




Modeling RF Devices using ASM - HEMT

- Extracting DC Parameters
 - RF Model Extraction
 - Large signal simulations
 - Load Pull Simulations

Extracting DC Parameters



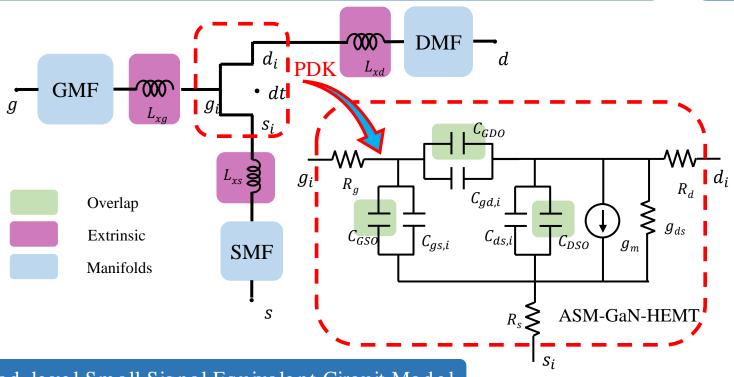
RF Model & Extraction I

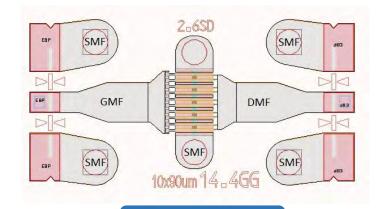
Three step methodology

- De-embed manifolds
- Extract the intrinsic core model Using low frequency Y-parameters
- Extract Inductances Using high frequency Y-parameters

Model

- Core surface potential based PDK
- Access region resistances included in core
- Bus-inductances in extrinsics





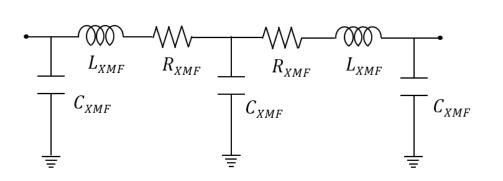
Device Layout

Pad-level Small Signal Equivalent Circuit Model

RF Model & Extraction II: Pad Parasitics

Manifolds/ Pads

- Used to probe the device
- Feed the signal to gate, drain & source bus-inductances
- Measurements obtained using TRL Calibration
- Transmission line type model
- Reciprocal (may/ may not be symmetric)
- De-embedded using "deembed" s 2p components in ADS



 R_{SMF} L_{SMF}

Re(Y_{xx}), Im(Y_{xy})
12 Real Y.,, Real Y. Imag Y,, Imag Y, Y-parameters for DMF Frequency (GHz) Re(Y_{xx}), Im(Y_{xx}) Y-parameters for GMF Frequency (GHz) Real Y ... Re(Y11) Y-parameters Imag Y, Model for SMF Frequency (GHz)

Symmetric network used for GMF/ DMF

Single port SMF network

RF Model & Extraction III: Bus Inductances

$$\begin{split} Y_{11} &= \frac{\omega^2 C_{gg}^{\ 2} R_g}{1 + \omega^2 C_{gg}^{\ 2} R_g^2} + \frac{j \omega C_{gg}}{1 + \omega^2 C_{gg}^{\ 2} R_g^2} \\ Y_{12} &= -\frac{\omega^2 C_{gd} C_{gg} R_g}{1 + \omega^2 C_{gg}^{\ 2} R_g^2} - \frac{j \omega C_{gd}}{1 + \omega^2 C_{gg}^{\ 2} R_g^2} \\ Y_{21} &= \frac{g_m - \omega^2 C_{gd} C_{gg} R_g}{1 + \omega^2 C_{gg}^{\ 2} R_g^2} - \frac{j \omega (C_{gd} + g_m C_{gg} R_g)}{1 + \omega^2 C_{gg}^{\ 2} R_g^2} \\ Y_{22} &= g_{ds} + \frac{\omega^2 (C_{gs} C_{gd} R_g + R_g C_{gd} C_{gg} (1 + g_m R_g))}{1 + \omega^2 C_{gg}^{\ 2} R_g^2} \\ + j \omega C_{ds} + \frac{j \omega C_{gd} (1 + g_m R_g) + j \omega^3 C_{gs} C_{gd} C_{gg} R_g^2}{1 + \omega^2 C_{gg}^{\ 2} R_g^2} \end{split}$$

Key Pointers

- The effect of bus-inductances is ignored at low frequencies (assumption)
- Drain & Source access region resistances ignored from hand analysis (not an assumption, it is an advantage)
- Ignore some terms at low frequency (~ 10 GHz)
 (assumption)
- Very simple only need to adjust overlap capacitances & gate finger resistances (advantage)

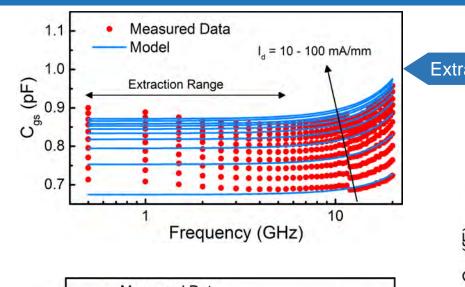
$$[\mathbf{Y}] \approx \begin{bmatrix} \omega^2 C_{gg}^{2} R_g + j\omega C_{gg} & -\omega^2 C_{gd} C_{gg} R_g - j\omega C_{gd} \\ g_m - j\omega \left(C_{gd} + g_m C_{gg} R_g \right) & g_{ds} + j\omega \left(C_{ds} + C_{gd} (1 + g_m R_g) \right) \end{bmatrix}$$

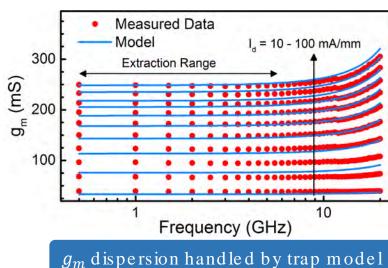
$$\begin{bmatrix} C_{\rm gs} & C_{\rm gd} & C_{\rm ds} \\ g_{\rm m} & g_{\rm ds} & R_{\rm g} \end{bmatrix}$$



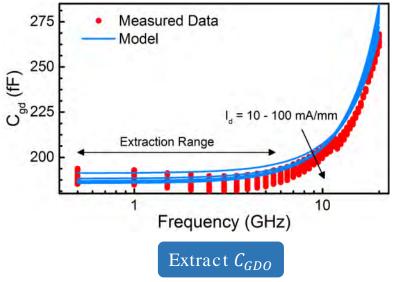
$$\begin{bmatrix} \left(\mathrm{Im}[Y_{11}] + \mathrm{Im}[Y_{12}]\right)/\omega & -\mathrm{Im}[Y_{12}]/\omega & \mathrm{Im}[Y_{22}]/\omega - C_{\mathrm{gd}}\left(1 + g_{\mathrm{m}}R_{\mathrm{g}}\right) \\ \mathrm{Re}[Y_{21}] & \mathrm{Re}[Y_{22}] & \mathrm{Re}[Y_{11}]/\left(\omega^{2}C_{\mathrm{gg}}^{2}\right) \end{bmatrix}$$

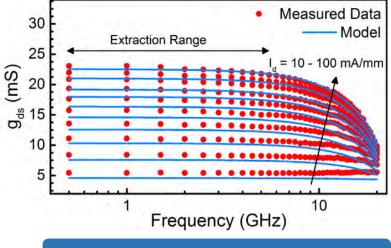
Fitting core model parameters using ADS





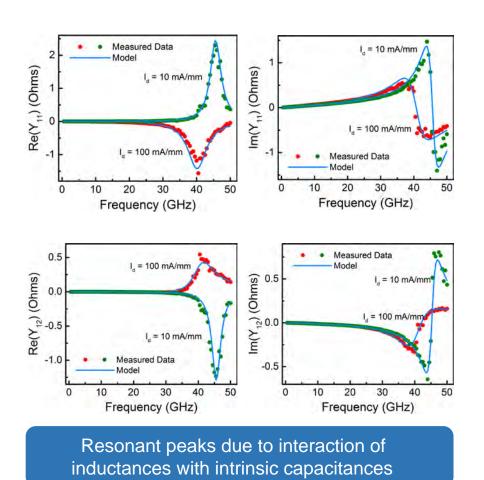
Extract C_{GSO}

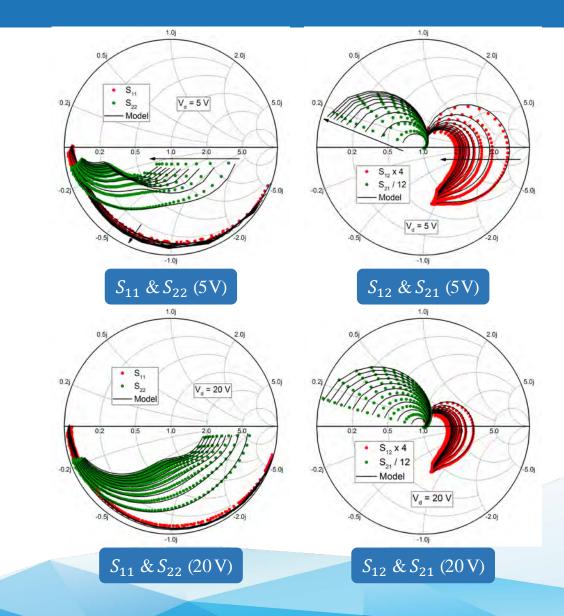




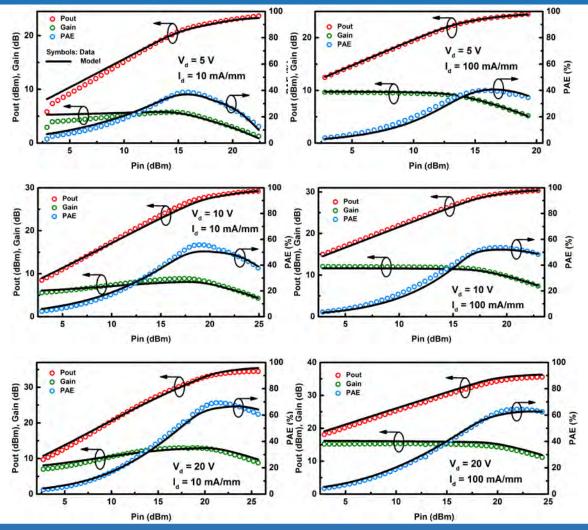
 g_{ds} dispersion handled by trap model

Bus Inductance fitting

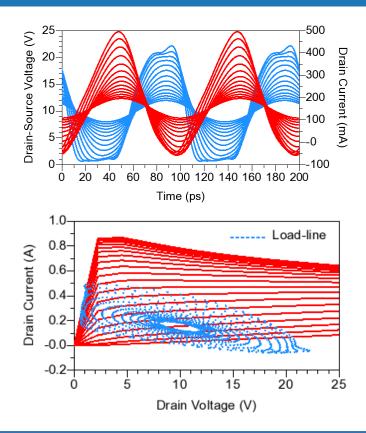




Large Signal HB Simulations



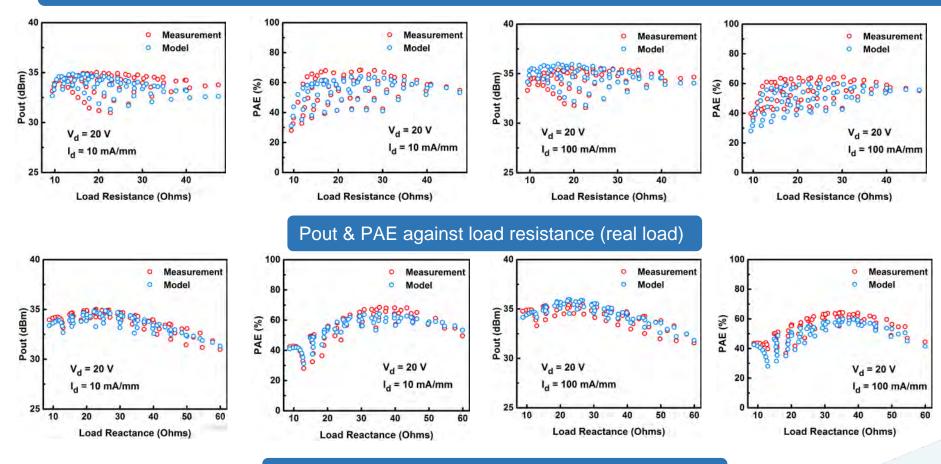
Harmonic balance drive -up characteristics showing Pout, PAE & Gain



Time domain waveforms of drain voltage & current. Load line contours spanning the IV plane

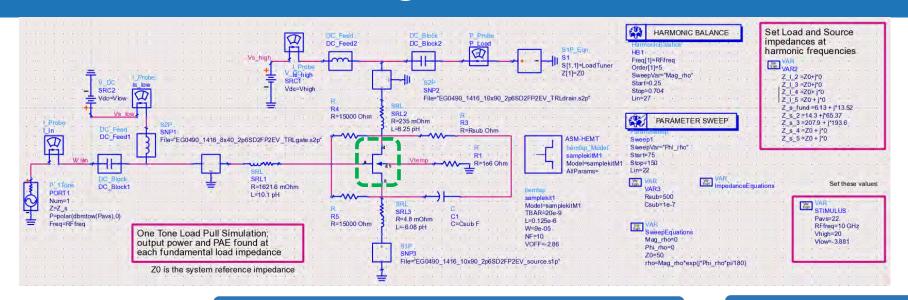
Validation – Real and Imaginary Loads

Fairly accurate in predicting the maxima for Pout & PAE



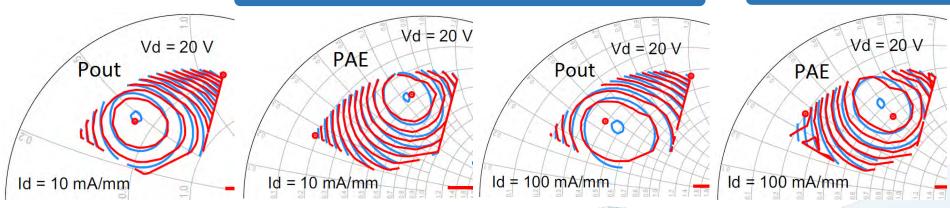
Pout & PAE against load reactance (imaginary load)

Load Pull simulations using ASM - HEMT



ADS Schematic for simulation of load -pull contours

22 dBm signal @ 10 GHz



Pout & PAE load pull contours for 10 mA/mm

Pout & PAE load pull contours for 100 mA/mm

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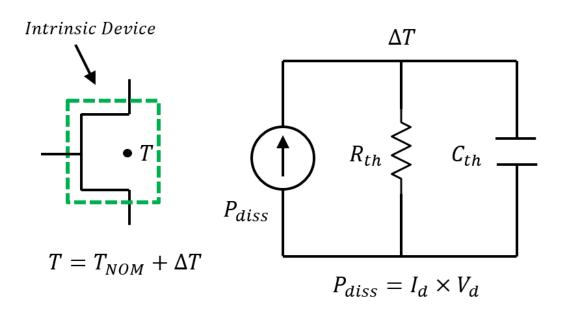




Characterizing Self Heating and its Modeling

- Self heating Model
 - Characterization

Self-Heating Model



Self-Heating Effect

- The self-heating circuit is defined in a thermal discipline.
- For the thermal discipline, power is the equivalent of "current" and temperature is the equivalent of "voltage"

Under these conditions, applying KCL on the thermal subcircuit, we have:

$$P(R_{th}) = \frac{Temp(R_{th})}{RTH0}$$

$$P(R_{th}) = \frac{d}{dt}(Temp(R_{th}) \cdot CTH0)$$

Characterization

$$T_{J1} = T_{NOM,1} + R_{th} \times P_{diss1}$$

$$T_{J2} = T_{NOM,2} + R_{th} \times P_{diss2}$$

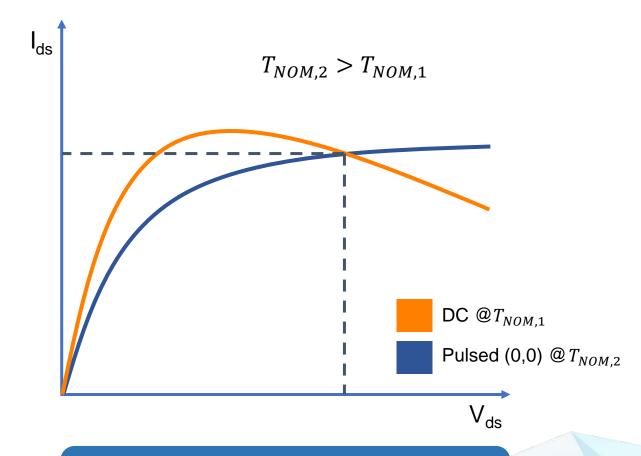
At the intersection point:

$$T_{J1} = T_{J2}$$

And $P_{diss2} = 0$ (Pulsed at (0,0))

$$\Rightarrow R_{th} = \Delta T_{NOM} / \Delta P_{diss}$$

With the ASM-HEMT model, the parameter RTH0 is tuned till the simulated intersection point overlaps with the measured intersection point after thermal parameters like UTE, AT and KT1 have been extracted.



Extracting R_{th} – Both curves are measured at the same Vgs. The intersection point denotes a common junction temperature.

[1] T. Peyretaillade et al.,1997 IEEE MTT-S International Microwave Symposium Digest, Denver, CO, USA, 1997. doi: 10.1109/MWSYM.1997.596619.

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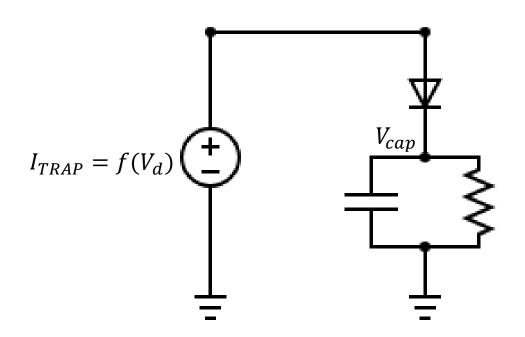




Trapping models in ASM - HEMT

- Trapping Models in ASM-HEMT
- Extraction using pulsed measurements

Trapping Models in ASM - HEMT: TRAPMOD I



Key highlights

- Dependent on drain voltage only
- Bias-dependent and bias-independent options
- Scales with signal power levels
- Suitable for RF
- Affects threshold voltage, DIBL, AR Resistance.

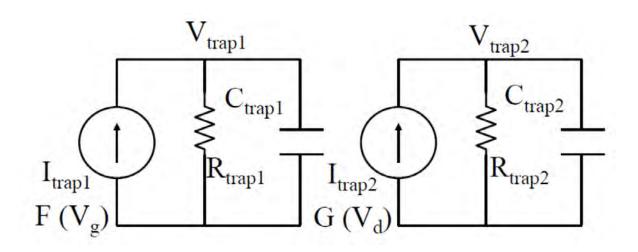
$$V_{OFF}(Trap) = V_{OFF} + (ATRAPVOFF + BTRAPVOFF \cdot e^{-\frac{1}{V_{Cap}}})$$

$$R_S(Trap) = R_S + (ATRAPRS + BTRAPRS \cdot e^{-\frac{1}{V_{cap}}})$$

$$R_D(Trap) = R_D + (ATRAPRD + BTRAPRD \cdot e^{-\frac{1}{V_{cap}}})$$

$$\eta_0(Trap) = \eta_0 + (ATRAPETA0 + BTRAPETA0 \cdot e^{-\frac{1}{V_{cap}}})$$

Trapping Models in ASM - HEMT: TRAPMOD II



Key highlights

- Dependent on both gate and drain voltages
- Modulates just the drain side access region resistance
- Suitable for PIV simulation
- Affects threshold voltage, DIBL, Subthreshold Slope,
 AR Resistance.

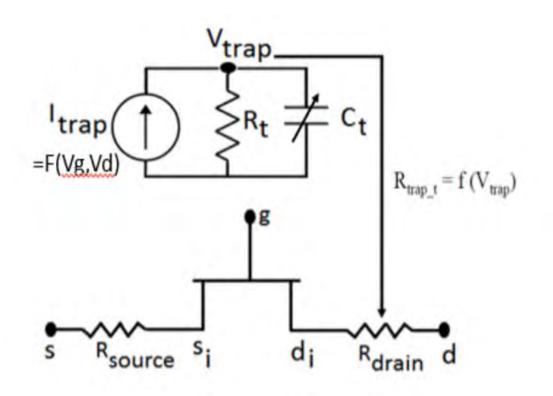
$$V_{OFF}(Trap) = V_{OFF} + (V_{OFFTR} \cdot V_{trap2})$$

$$\eta_0(Trap) = \eta_0 + (\eta_{0TR} \cdot V_{trap2})$$

$$C_{DSCD}(Trap) = C_{DSCD} + (C_{DSCDTR} \cdot V_{trap2})$$

$$R_{ds}(Trap) = R_{ds} - (R_{TR1} \cdot V_{trap1}) + (R_{TR2} \cdot V_{trap2})$$

Trapping Models in ASM - HEMT: TRAPMOD III

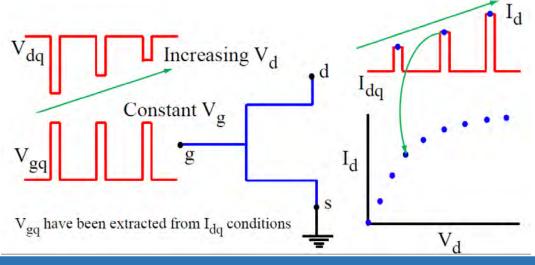


Ke y highlights

- Dependent on both gate and drain voltages
- Modulates just the drain side access region resistance for dynamic Ron
- Suitable for simulating Power Devices
- Incorporates temperature dependence.

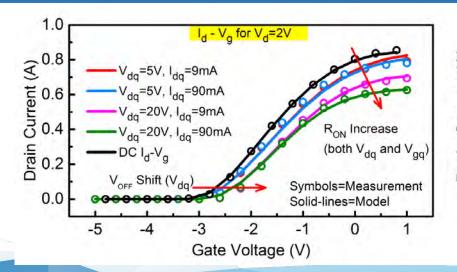
$$R_D(Trap) = R_D + \frac{V(trap1)}{VATRAP} \cdot \left(\frac{T_{dev}}{T_{NOM}}\right)^{TALPHA}$$

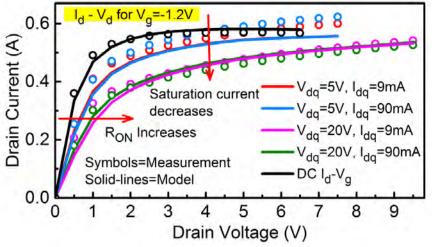
Extraction using pulsed measurements



- Pulsed IV characterization in dual-pulse mode at a pulse frequency of 1000 Hz with a duty-cycle of 0.02 % is performed under multiple quiescent drain and gate bias conditions such that both the gate and the drain voltages are pulsed simultaneously from the quiescent bias point.
- The pulse width of 200 ns and the measurement window of 40 ns within these 200 ns is short enough to ensure isothermal and iso-dynamic measurement of the pulsed-IV characteristics.

Pulsed-IV Scheme used to simulate the P-IV Characteristics





Pulsed – IV chacteristics for multiple quiescent conditions – using TRAPMOD II





Related Publications

- S. Khandelwal, Y. S. Chauhan, T. A. Fjeldly, S. Ghosh, A. Pampori, D. Mahajan, R. Dangi, and S. A. Ahsan, "ASM GaN: Industry Standard Model for GaN RF and Power Devices Part-I: DC, CV, and RF Model", IEEE Transactions on Electron Devices, 2019.
- S. A. Albahrani, D. Mahajan, J. Hodges, Y. S. Chauhan, and S. Khandelwal, "<u>ASM GaN: Industry Model for GaN RF and Power Devices Part-II: Modeling of Charge Trapping</u>", IEEE Transactions on Electron Devices, 2019.
- A. Pampori, S. A. Ahsan, S. Ghosh, S. Khandelwal, and Y. S. Chauhan, "https://physics-based Compact Modeling of MSM-2DEG GaN-based Varactors for THz Applications", IEEE Electron Devices Technology and Manufacturing Conference (EDTM), Kobe, Japan, Mar. 2018.
- S. A. Ahsan, A. Pampori, S. Ghosh, S. Khandelwal, and Y. S. Chauhan, "<u>A New Small-signal Parameter Extraction Technique for large gate-periphery GaN HEMTs</u>", IEEE Microwave and Wireless Components Letters, Vol. 27, Issue 10, Oct. 2017.
- S. A. Ahsan, S. Ghosh, S. Khandelwal, and Y. S. Chauhan, "Physics-based Multi-bias RF Large-Signal GaN HEMT Modeling and Parameter Extraction Flow", IEEE Journal of the Electron Devices Society, Vol. 5, Issue 5, Sept. 2017.
- S. A. Ahsan, S. Ghosh, S. Khandelwal, and Y. S. Chauhan, "Pole-Zero Approach to Analyze and Model the Kink in Gain-Frequency Plot of Gan HEMTs", IEEE Microwave and Wireless Components Letters, Vol. 27, Issue 3, Mar. 2017.
- S. A. Ahsan, S. Ghosh, S. Khandelwal, and Y. S. Chauhan, "<u>Analysis and Modeling of Cross-Coupling and Substrate Capacitance in GaN HEMTs for Power-Electronic Applications</u>", IEEE Transactions on Electron Devices (Special Issue), Vol. 64, Issue 3, Mar. 2017.
- S. Ghosh, S. A. Ahsan, S. Khandelwal, A. Pampori, R. Dangi, and Y. S. Chauhan, "Physics Based Analysis and Modeling of Capacitances in a Dual Field Plated Power Gan HEMT", International Workshop on Physics of Semiconductor Devices (IWPSD), Delhi, India, Dec. 2017.
- S. A. Ahsan, S. Ghosh, S. Khandelwal, A. Pampori, R. Dangi, and Y. S. Chauhan, "<u>A Scalable Physics-based RF Large Signal Model for Multi-finger GaN HEMTs</u>", International Workshop on Physics of Semiconductor Devices (IWPSD), Delhi, India, Dec. 2017.
- S. Khandelwal, S. Ghosh, S. A. Ahsan and Y. S. Chauhan, "<u>Dependence of GaN HEMT AM/AM and AM/PM Non-Linearity on AlGaN Barrier Layer Thickness</u>", IEEE Asia Pacific Microwave Conference (APMC), Kuala Lumpur, Malaysia, Nov. 2017.

- S. A. Ahsan, S. Ghosh, S. Khandelwal and Y. S. Chauhan, "<u>Surface-potential-based Gate-periphery-scalable Small-signal Model for GaN HEMTs</u>", IEEE Compound Semiconductor IC Symposium (CSICS), Miami, USA, Oct. 2017.
- S. A. Ahsan, S. Ghosh, A. Dasgupta, K. Sharma, S. Khandelwal, and Y. S. Chauhan, "<u>Capacitance Modeling in Dual Field Plate Power GaN HEMT for Accurate Switching Behaviour</u>", IEEE Transactions on Electron Devices, Vol. 63, Issue 2, Feb. 2016.
- S. Ghosh, S. A. Ahsan, A. Dasgupta, S. Khandelwal, and Y. S. Chauhan, "Gan HEMT Modeling for Power and RF Applications using ASM-HEMT", IEEE International Conference on Emerging Electronics (ICEE), Mumbai, India, Dec. 2016.
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Thank You!

Questions